

Docket Number: 081468-0304531
Client Reference: P-1806.000-US

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re the Application of

JOZEF MARIA FINDERS et al.

Group Art Unit:

Application No.: TO BE ASSIGNED

Examiner:

Filed: January 28, 2004

Confirmation No.:

For: ENHANCED LITHOGRAPHIC RESOLUTION THROUGH DOUBLE EXPOSURE

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents
P. O. Box 1450
Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR 1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

The undersigned respectfully notes that copies of U.S. references are not required in applications filed after June 30, 2003

This Information Disclosure Statement is being filed (a) within three months of the U.S. filing date of this non-CPA application, OR (b) before the mailing date of the first Office Action on the merits in the present application. No certification or fee is required.

Respectfully Submitted,

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M#

Client Ref.

304531

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT

Applicant: FINDERS et al.

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Examiner:

Group Art Unit:

U.S. PATENT DOCUMENTS

Examiner's Initials*		Document Number	Date MM/YYYY	Name (Family Name of First Inventor)	Class	Sub Class	Filing Date (if appropriate)
	AR	6,042,998	03/2000	BRUECK et al.			
	BR	6,320,648	11/2001	BRUECK et al.			
	CR						
	DR						
	ER						
	FR						
	GR						
	HR						
	IR						
	JR						
	KR						
	LR						
	MR						
	NR						

FOREIGN PATENT DOCUMENTS

		Document Number	Date MM/YYYY	Country	Inventor Name		Abstract		Readily Available	
							Enclosed	No	Enclose	No
	OR									
	PR									
	QR									
	RR									
	SR									
	TR									

OTHER (Including in this order Author, Title, Periodical Name, Date, Pertinent Pages, etc.)

	UR	Ooki et al., "A Novel Super-Resolution Technique for Optical Lithography – Nonlinear Multiple Exposure Method," <i>Jpn. J. Appl. Phys.</i> 33:L177 – L179 (1994)				
	VR					
	WR					
	XR					
	YR					
	ZR					
	AAR					
	BBR					
	CCR					

Examiner

Date Considered:

*EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP § 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.